

LLO Labo Kit



UV laser LLO R&D system LSL-10

Application

- LLO for Flexible OLED
- LLO for ultra thin Si wafer
- LLO for organic semiconductor device
- LLO for flexible device as sensor and detector



Flexible display



Ultra thin Si wafer



Flexible organic device

Feature of the system

Using DPSS UV Laser with special optics unit to make homogeneous Line Beam to irradiate the work by moving X-Y stage to LLO for where area as R&D purpose.

1. Very Low Price and ultra compact system
2. Can be use with 100V AC only. (less than 15A)
3. Option for Laser Film Cutting

Specification

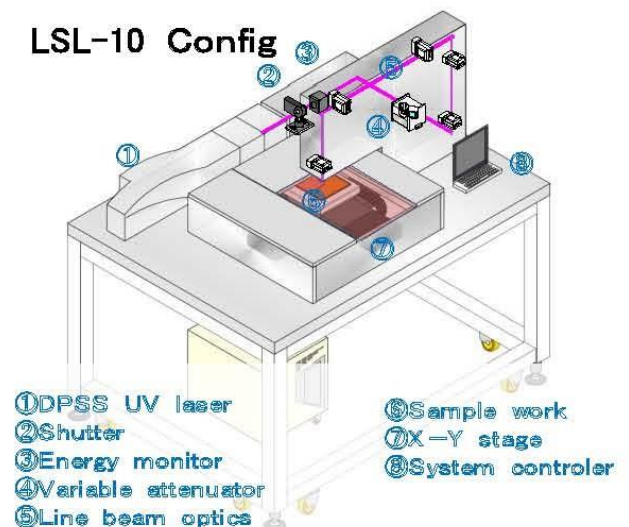
Wavelength	355nm
Line beam size	40mm x 0.4mm
Process energy density	25~250mJ/cm ² (Variable attenuator)
Beam Overlap	0%~98% (Stage control)
Work size(mm)	Max150 x150 Option: G2(370 x470)
Process speed	5 min (100mm panel)
Stage stroke	200mm x200mm
System size (mm)	L1200 x W900 x H1500
Utility	AC100V ±10% 15A



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LLO(1 row)

LSL-10 Config



Note. This is Lab system and class 4 laser product. Please use in the laser management area

